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FORM PTO - 1449	ATTY DOCKET NO.:	ASX-015C4
INFORMATION DISCLOSURE STATEMENT	APPLICANTS:	Smith et al.
	SERIAL NO.:	Not yet assigned.
	FILING DATE:	Herewith
	GROUP:	Not yet assigned.

COPY

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hm	AA	5,290,382	03/01/94	Zarowin et al.			
	AB	3,343,022	09/19/67	Eckert			
	AC	4,431,901	02/14/84	Hull			
	AD	4,878,149	10/31/89	Stiehl et al.			
	AE	5,346,578	09/13/94	Benzing et al.			
	AF	5,401,350	03/28/95	Patrick et al.			
	AG	5,405,480	04/11/95	Benzing et al.			
	AH	5,430,355	07/04/95	Paranjpe			
	AI	5,468,296	11/21/95	Patrick et al.			
	AJ	5,479,072	12/26/95	Dakin et al.			
	AK	5,506,507	04/09/96	Schwierzke et al.			
	AL	5,514,246	05/07/96	Blalock			
	AM	3,500,118	03/10/70	Anderson			
	AN	3,663,361	05/16/72	Yoshikawa			
	AO	3,987,334	10/19/76	Anderson			
	AP	4,088,926	05/09/78	Fletcher et al.			
	AQ	4,180,763	12/25/79	Anderson			
	AR	4,252,609	02/24/81	Kerst et al.			
	AS	4,626,400	12/02/86	Jassby et al.			
	AT	4,689,192	08/25/87	Nagata			
	AU	5,254,830	10/19/93	Zarowin et al.			
	AV	5,336,355	08/09/94	Zarowin et al.			
	AW	5,556,549	09/17/96	Patrick et al.			
	AX	5,630,880	05/20/97	Eastlund			
	AY	H554	12/06/88	Dawson et al.			
W	AZ	4,431,898	02/14/84	Reinberg et al.			

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	A3	4,049,940	09/20/97	Moisan et al.			
	A4	4,065,369	12/27/77	Ogawa et al.			
	A5	4,285,800	08/25/81	Welty			
	A6	4,324,611	04/13/82	Vogel et al.			
	A7	4,350,578	09/21/82	Frieser et al.			
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	A9	4,461,954	07/24/84	Inoue			
	A10	4,631,105	12/23/86	Carroll et al.			
	A11	4,668,336	05/26/87	Shimkunas			
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	A13	4,793,975	12/27/88	Drage			
	A14	4,810,933	03/07/89	Moisan et al.			
	A15	4,853,250	08/01/89	Boulos et al.			
	A16	4,859,908	08/22/89	Yoshida et al.			
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	A18	4,906,898	03/06/90	Moisan			
	A19	4,948,458	08/14/90	Ogle			
	A20	5,000,771	03/19/91	Fleming, Jr. et al.			
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	A22	5,016,332	05/21/91	Reichelderfer, deceased et al.			
	A23	5,099,100	03/24/92	Bersin et al.			
	A24	5,144,196	09/01/92	Gegenwart et al.			
	A25	5,180,150	01/19/93	Prusak et al.			
	A26	5,198,718	03/30/93	Davis et al.			

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	A27	5,206,516	04/27/93	Keller et al.			
	A28	5,280,154	01/18/94	Cuomo et al.			
	A29	5,352,249	10/04/94	Vollaro			
	A30	5,353,314	10/04/94	Schaffer			
	A31	5,364,496	11/15/94	Bollinger et al.			
	A32	5,365,147	11/15/94	Shinohara et al.			
	A33	5,372,674	12/13/94	Steinberg			
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	A35	5,397,962	03/14/95	Moslehi			
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	A64	5,892,198	04/06/99	Barnes et al.			
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	A71	5,406,177	04/11/95	Nerone			
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	A73	4,786,352	11/22/88	Benzing			
	A74	4,859,399	08/22/89	Bussard			
	A75	5,030,889	07/09/91	El-Hamamsy et al.			
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	BB	SU957744 A1	02/10/96	SU				N	Y-Abstract
	BC	02260399	10/23/90	JP				Y	Y
	BD	5-166595	07/02/93	JP				N	Y-Abstract
	B1	61-139029	6/26/86	JP				N	Y-Abstract
	B2	5-144594	06/11/93	JP				N	Y-Abstract
	B3	2-260399	10/23/90	JP				N	Y-Abstract
M	B4	2022917	11/15/94	RU			9/27/89	No	Yes (Translation)

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	GROUP:	Not yet assigned.

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	APPLICANTS:	Smith et al.
	SERIAL NO.:	Not yet assigned.
	FILING DATE:	Herewith
	GROUP:	Not yet assigned.

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EXAMINER		DATE CONSIDERED	7/10/06

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FORM PTO - 1449 SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT	ATTORNEY DOCKET NO.: ASX-015C4 APPLICANTS: Smith et al. SERIAL NO.: 10/689,165 FILING DATE: October 20, 2003 GROUP: Not yet assigned.

U.S. PATENT DOCUMENTS

EXAM. INIT.		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
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EXAMINER		DATE CONSIDERED	7/10/06

FORM PTO - 1449 SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT	ATTORNEY DOCKET NO.: ASX-015C4 APPLICANTS: Smith et al. SERIAL NO.: 10/689,165 FILING DATE: October 20, 2003 GROUP: Not yet assigned.

U.S. PATENT DOCUMENTS

EXAM. INIT.		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
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	A102	4,908,492	03/13/90	Okamoto et al.			
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	A117	5,712,592	01/27/98	Stimson et al.			
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	A119	5,756,400	05/26/98	Ye et al.			
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	A122	5,939,886	08/17/99	Turner et al.			
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EXAMINER		DATE CONSIDERED	5/10/06

FORM PTO - 1449 SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT	ATTORNEY DOCKET NO.: ASX-015C4 APPLICANTS: Smith et al. SERIAL NO.: 10/689,165 FILING DATE: October 20, 2003 GROUP: Not yet assigned.

U.S. PATENT DOCUMENTS

EXAM. INIT.		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
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M	A125	6,164,241	12/26/00	Chen et al.			
M	A126	6,253,704	07/03/01	Savas			9/17/99

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EXAM. INIT.		DOCUMENT NUMBER	DATE	COUNTRY CODE	CLASS	SUB CLASS	FILING DATE	ABSTRACT ONLY	ENGLISH LANG (Y/N)
M	B6	61-1024	01/07/86	JP			06/12/84	N	Original and translation provided by Advanced Energy Industries, Inc. during litigation with Assignee

OTHER ART, JOURNAL ARTICLES, ETC.

EXAM. INIT.		OTHER DOCUMENTS: (Including Author, Title, Date, Relevant Pages, Place of Publication)
M	C122	Complaint for Declaratory Judgment of Non-Infringement, filed in the United States District Court for the District of Colorado, by Advanced Energy Industries, Inc., dated April 3, 2003.
M	C123	Complaint, filed in the United States District Court for the District of Delaware, by MKS Instruments, Inc. and Applied Science and Technology, Inc., dated May 14, 2003
M	C124	Answer, filed in the United States District Court for the District of Delaware, by Advanced Energy Industries, Inc., dated December 10, 2003.
M	C125	Amended Complain and Jury Demand, filed in the United States District Court for the District of Colorado, by Advanced Energy Industries, Inc., dated December 15, 2003.

EXAMINER	DATE CONSIDERED 7/10/06

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